

## SiwoPUD-920F<sup>®</sup>

**Characteristics:** Aqueous, aliphatic polyurethane dispersion based on poly(ester+carbonate).

**Supplied as:** 37% in water

<b>Physical characteristics:</b>	Appearance	Translucence
	Non-volatile constituent	37±1 %
	PH value	7.0 - 9.5
	Viscosity	≤300mPa s
	Mean particle size	≤100 nm
	Minimum film-forming temperature	60°C
	NMP, NEP, DMAC	Free
	Shore A Hardness	86
	Gloss (60° )	90.5 (Add 1%DPM and 2%DPnB)
	Shear stability	Good
	Dry	Fast
	Yellowing resistance	Non- yellowing

**Storage:** The dispersion should be stored in a frost-free place in tightly sealed containers. It contains no preservative.

**Application:** Anionic waterborne polyurethane dispersion with high molecular weight. It has excellent resistance to water, alkali, hydrolysis and weather fastness. It has high hardness, excellent wear resistance and high brightness. In terms of chemical structure, it has better crosslinking degree and chemical resistance. It can be widely used in wood, floor, metal, and wall coatings, as well as acrylic emulsion modification. It does not contain organotin compounds, heavy metals, formaldehyde, etc. It can be added nitrogen pyridine crosslinker and water-dispersible polyisocyanate crosslinker to further improve the properties.

It is recommended to add 1% dipropylene glycol monomethyl ether (DPM) and 2% dipropylene glycol monobutyl ether (DPnB) as film forming agent. The film can be formed at room temperature without heating.

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